

L Number	Hits	Search Text	DB	Time stamp
1	17634	micromachine or microelectromechanical or MEMS	USPAT; EPO; JPO; IBM_TDB	2003/06/16 13:57
2	86	("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") same polysilicon same (resist or photoresist or pattern\$3) same (conduit or channels or rails) same (HF or hydrofluoric)	USPAT; EPO; JPO; IBM_TDB	2003/06/16 14:04
3	3466	("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric)	USPAT; EPO; JPO; IBM_TDB	2003/06/16 15:34
4	139	(micromachine or microelectromechanical or MEMS) and (("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric))	USPAT; EPO; JPO; IBM_TDB	2003/06/16 14:05
6	1		USPAT	2003/06/16 14:23
9	648	("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric) and sacrificial	USPAT; EPO; JPO; IBM_TDB	2003/06/16 15:19
10	77	(("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric) and sacrificial) and MEMS	USPAT; EPO; JPO; IBM_TDB	2003/06/16 15:19
12	403	("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and (SiN or "silicon nitride" ) and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric) and (release or released or releasing)	USPAT; EPO; JPO; IBM_TDB	2003/06/16 16:48
13	369	(("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and (SiN or "silicon nitride" ) and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric) and (release or released or releasing)) and semiconductor	USPAT; EPO; JPO; IBM_TDB	2003/06/16 16:14
14	1	5867302.pn.	USPAT; EPO; JPO; IBM_TDB	2003/06/16 16:14
15	67	(micromachine or microelectromechanical or MEMS) and ("silicon oxide" or SiO or "silicon dioxide" or "SiO.sub.2") and (SiN or "silicon nitride" ) and polysilicon and (resist or photoresist or pattern\$3) and (conduit or channels or rails) and (HF or hydrofluoric) and (release or released or releasing)	USPAT; EPO; JPO; IBM_TDB	2003/06/16 16:49